

Process for patterning non-photoimagable ceramic tape

Description of Technology: The invention is directed to a process for patterning non-photoimagable ceramic tape utilizing photoresist technology wherein the photoresist, after imagewise exposure and development, acts as a development mask for the ceramic tape.

Patent Listing:

1. **US Patent No. 6,653,056**, Issued November 25, 2003, "Process for patterning non-photoimagable ceramic tape"

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Market Potential: Ceramic green tapes have long been used as dielectric substrates in hybrid circuit fabrication and are now being used in an emerging technology of flat panel display development. Forming via holes or barrier rib patterns on the tape is currently done by mechanical processes such as die punching or sandblasting. However, as the industry trend moves toward finer feature sizes and more complicated patterns, mechanical patterning processes fall short in meeting this trend.

Benefits:

• Tape is more durable and easier to handle

Applications:

• Patterning non-photoimagable ceramic tape